

CITY OF MOUNTAIN VIEW  
APPLICATION FOR INDUSTRIAL WASTES DISCHARGE PERMIT

SFUND RECORDS CTR  
2807-91380

Date 11-10-83

No. \_\_\_\_\_

A. Name or Organization NEC ELECTRONICS U.S.A. INC.

Address 550 EAST MIDDLEFIELD ROAD, MOUNTAIN VIEW, CA 94043

Address of Point of Discharge 501 ELLIS STREET, MOUNTAIN VIEW, CA 94043

Individual Responsible Name MICHAEL KIERIG

for Industrial Waste Signature \_\_\_\_\_

Attach Map Showing Point of Discharge, Sampling Points, and Waste Treatment Facility

SFUND RECORDS CTR  
**88171555**

(415) 964-4321

Telephone \_\_\_\_\_

B. ☒ Flow Rate: Average \_\_\_\_\_ gals/day Max. 122,010 gals/day Peak Hourly \_\_\_\_\_ GPM

C. Submit separate statement:

1. Detailing type of industry and nature of products
2. Listing chemicals used and approximate concentrations
3. Describing waste treatment facilities
4. Giving characteristics of exceptional industrial wastes
5. Concerning radioactive wastes
6. Naming organic solvents discharged and concentration at point of discharge

D. Indicate the point of discharge concentration of the following characteristics and mass emission rates where applicable.

Biochemical oxygen demand (B.O.D.)	<u>&lt; 2</u> mg/l	Grease and oil, total	<u>&lt; 0.1</u> mg/l
Chemical oxygen demand (C.O.D.)	<u>29</u> mg/l	Hydrogen Ion content pH	<u>7.8</u>
Total Solids, Average	<u>&lt; 1</u> mg/l	Fluoride	<u>1.6</u> mg/l
Suspended Solids, Average	<u>0.03</u> mg/l	Temperature	<u>60-65 °F</u>

	Max. Conc. Allowable mg/l	Allowable Mass Emission Rate kg/day		Ad V. Max. Conc. Allowable mg/l	Ad V. Conc. Allowable Mass Emission Rate kg/day
Arsenic	<u>0.1</u>	<u>0.001</u>	Cyanides	<u>1.0</u>	<u>&lt; 0.02</u>
Barium	<u>5.0</u>	<u>&lt; 0.1</u>	Formaldehyde	<u>5.0</u>	<u>&lt; 0.1</u>
Beryllium	<u>1.0</u>	<u>&lt; 0.0001</u>	Lead	<u>0.5</u>	<u>0.003</u>
Boron	<u>1.0</u>	<u>&lt; 0.1</u>	Manganese	<u>1.0</u>	<u>0.0064</u>
Cadmium	<u>0.1</u>	<u>&lt; 0.0001</u>	Mercury	<u>0.05</u>	<u>&lt; 0.0001</u>
Chromium Hexavalent	<u>1.0</u>	<u>0.002</u>	Nickel	<u>1.0</u>	<u>&lt; 0.02</u>
Chromium Total	<u>2.0</u>	<u>&lt; 0.01</u>	Phenols	<u>1.0</u>	<u>1.2</u>
Cobalt	<u>1.0</u>	<u>&lt; 0.001</u>	Selenium	<u>2.0</u>	<u>&lt; 0.001</u>
Copper	<u>2.0</u>	<u>&lt; 0.01</u>	Silver	<u>5.0</u>	<u>&lt; 0.0001</u>
Cresols	<u>2.0</u>	<u>&lt; 0.05</u>	Zinc	<u>5.0</u>	<u>&lt; 0.01</u>

NOT TO BE COMPLETED BY APPLICANT

Permit to Discharge Industrial Wastes in Accordance with This  
Application Subject to Attached General and Specific Conditions

Maintenance Director \_\_\_\_\_

Date \_\_\_\_\_

Permit to Discharge Exceptional Industrial Waste Approved

List Details:

Maintenance Director \_\_\_\_\_

**379**

Date \_\_\_\_\_

1. NEC Electronic U. S. A. Inc., - Semiconductor manufacturer, 501 Ellis Street Mountain View is the current sole location for Wafer Fabrication.

2. Chemical currently in use at this facility:

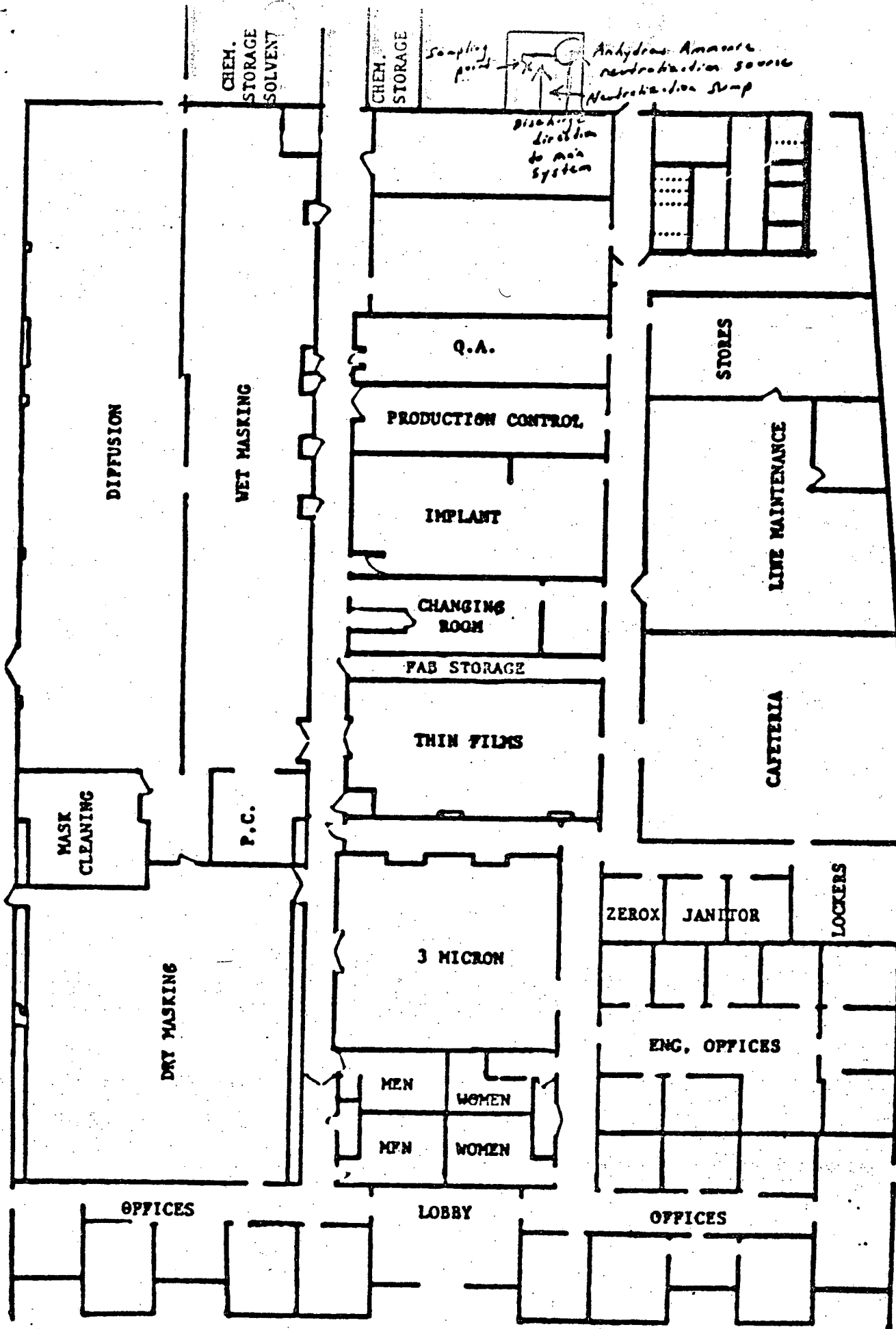
- Glacial Acetic Acid (100%)
- Nitric Acid (to 70%)
- Phosphoric Acid (85%)
- Sulfuric Acid (95%)
- Hydrochloric Acid (70%)
- Hydrofluoric Acid (to 49%)
- Ammonium Fluoride (58%)
- Ammonium Phosphate (100%)
- Hydrogen Peroxide (30%)
- Hexamethyl Disilazane (up to 50%)
- Isopropyl Alcohol
- 1,1,1 Trichloroethane 1,1,2 Trichloro 1,2,2,
- Trifluoroethane
- Toluene
- Xylene
- Methyl Alcohol
- N-Butyl Acetate
- Burnar 712 D
  - . < 25% Phenol
  - . < 50% Trichlorobenzene
  - . < 25% Sulfonic Acid
  - . < 25% Other Aromatics
- Acetone
- KTI Positive Photoresist Stripper R-10
  - . 70% Diethylene glycol monobutyl ether
  - . 30% Ethanol Amine

3. Waste treatment facility consists of acid neutralization sump, utilizing anhydrous ammonia as the agent.

4. \_\_\_\_\_

5. \_\_\_\_\_

6. KTI Positive Photoresist Stripper R-10 at 960 gallons/year.



501 ELLIS STREET